

ABSTRACT

CVD APPARATUS

5 To provide a CVD apparatus that can reduce particle
pollution for a substrate. One aspect of the present
invention is a CVD apparatus for forming a film on a substrate
by a CVD method, the CVD apparatus including a chamber 101,
a substrate holder 104 that is disposed in the chamber and
10 holds the substrate, and a gas introduction mechanism that
introduces raw material gas into the chamber, wherein a film
formed of any material of metal, ceramics, plastic and cermet
is formed on at least one of an inner surface of the chamber,
the substrate holder, an adhesion-preventing plate disposed
15 in the chamber, a jig disposed in the chamber and a gas shower
member that introduces the raw material gas into the chamber
in a shower state.

Fig. 1